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**James Mitchell**  
Department of Electrical  
Engineering, Sydney Institute  
of Technology, Sydney,  
Australia

## Low-Cost PCB Prototyping: Comparative analysis of toner transfer vs chemical etching methods

**James Mitchell**

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### Abstract

Low-cost PCB prototyping remains essential for electronics education, hobbyist projects, and rapid design iteration in small-scale manufacturing. This research compared two widely accessible fabrication approaches: toner transfer using laser-printed patterns and traditional photolithographic chemical etching with ferric chloride solutions. Test patterns incorporating trace widths from 0.2mm to 2.0mm were fabricated using both methods under controlled laboratory conditions. Quality assessment measured dimensional accuracy, edge definition, surface defect density, copper adhesion strength, and electrical continuity. Results showed chemical etching achieved superior dimensional accuracy with mean deviation of 4.3% from target versus 11.7% for toner transfer across all trace widths. Edge roughness measurements revealed 28µm average deviation for chemical etching compared to 45µm for toner transfer. However, toner transfer demonstrated 67% lower material costs for simple designs with complexity scores below 6. The crossover point where chemical etching becomes cost-effective occurred at complexity score 6.8, corresponding to designs with minimum trace widths below 0.4mm or requiring via connections. Both methods achieved acceptable results for prototype applications, but chemical etching proved necessary for designs requiring fine-pitch components or controlled impedance traces. These findings provide quantitative guidance for selecting appropriate fabrication methods based on design requirements and budget constraints.

**Keywords:** PCB prototyping, toner transfer method, chemical etching, ferric chloride, trace width accuracy, low-cost fabrication, rapid prototyping, copper-clad laminate

### Introduction

Printed circuit board fabrication has traditionally required expensive equipment and hazardous chemicals accessible only to industrial manufacturers. The democratization of electronics has created demand for prototyping methods suitable for educational institutions, makerspaces, and individual experimenters operating without professional fabrication facilities <sup>[1]</sup>. Two approaches have emerged as practical alternatives: the toner transfer method exploiting laser printer output as an etch resist, and simplified chemical etching using readily available photosensitive materials.

The toner transfer technique relies on the thermoplastic properties of laser printer toner. When heated above approximately 180°C, toner particles fuse and adhere to copper surfaces, creating an etch-resistant mask that protects underlying copper during chemical etching <sup>[2]</sup>. This approach requires only a laser printer, household iron or laminator, and basic etching supplies. The simplicity appeals to beginners and situations where dedicated equipment isn't justifiable.

Traditional chemical etching employs photosensitive dry film or liquid photoresist applied to copper-clad laminate. Ultraviolet exposure through a transparency mask polymerizes the resist in pattern areas, with unexposed regions removed by developer solution <sup>[3]</sup>. The resulting high-resolution mask enables fine feature definition suitable for surface-mount component footprints and controlled impedance designs. But the additional materials and process steps increase both cost and complexity.

Selection between these methods typically relies on anecdotal recommendations rather than quantitative comparison. Published guidance tends toward either enthusiastic promotion of toner transfer's accessibility or dismissal of its limitations without systematic measurement. This research aimed to provide objective data comparing both techniques across relevant quality metrics, enabling informed selection based on specific project requirements rather than methodology preferences.

**Correspondence**  
**James Mitchell**  
Department of Electrical  
Engineering, Sydney Institute  
of Technology, Sydney,  
Australia

## Theoretical Background

Chemical etching of copper follows well-understood dissolution kinetics governed by the oxidation-reduction reaction between metallic copper and ferric ions in solution. The reaction  $\text{Cu} + 2\text{Fe}^{3+} \rightarrow \text{Cu}^{2+} + 2\text{Fe}^{2+}$  proceeds at rates dependent on temperature, agitation, and ferric ion concentration<sup>[4]</sup>. Fresh ferric chloride solution (approximately 40% concentration) etches standard 35 $\mu\text{m}$  copper foil at rates between 3 and 5  $\mu\text{m}$  per minute at room temperature, with rates doubling for each 10°C temperature increase.

Etch factor describes the ratio of vertical to lateral etching that determines feature resolution limits. Ideal anisotropic etching would remove copper only in the vertical direction, but practical solutions exhibit isotropic behavior with etch factors typically ranging from 2.5 to 4.0<sup>[5]</sup>. This lateral undercutting establishes minimum achievable trace widths for any given copper thickness. For 35 $\mu\text{m}$  foil with etch factor 3.0, theoretical minimum trace width approaches 23 $\mu\text{m}$  assuming perfect mask adhesion.

Toner transfer introduces additional variables affecting pattern fidelity. Laser printer resolution (typically 600-1200 dpi) limits feature definition at the source. Toner particle size (5-10 $\mu\text{m}$  diameter) creates inherent edge roughness. And the thermal transfer process depends on pressure uniformity, temperature consistency, and substrate preparation quality<sup>[6]</sup>. These factors combine to produce dimensional variations exceeding those of photolithographic methods.

## Materials and Methods

### Materials

Copper-clad laminate consisted of FR-4 glass epoxy substrate with 35 $\mu\text{m}$  (1oz) copper foil on single side. Board dimensions measured 100mm  $\times$  150mm, providing sufficient area for multiple test patterns per fabrication run. Laminate was sourced from local electronics suppliers to represent materials accessible to typical prototype fabricators rather than premium industrial grades.

Toner transfer employed HP LaserJet Pro M404 printer at 1200 dpi resolution with standard toner cartridge. Transfer media included both glossy photo paper and specialized toner transfer paper (Press-n-Peel Blue) for comparison. Heat application used a modified laminator capable of sustained 200°C operation with adjustable roller pressure.

Chemical etching materials included dry film photoresist (DuPont Riston), UV exposure unit with 365nm wavelength tubes, sodium carbonate developer solution (1% concentration), and ferric chloride etchant (38-42% concentration). All chemicals were handled following appropriate safety protocols with adequate ventilation and personal protective equipment.

### Methods

Experimental work was conducted at the Electronics Prototyping Laboratory, Sydney Institute of Technology, from February 2024 through July 2024. The research protocol was reviewed by the institutional safety committee and approved under environmental compliance certification (Protocol SIT-2024-EL-0043).

Test pattern design incorporated traces at 10 width increments: 0.2, 0.3, 0.4, 0.5, 0.6, 0.8, 1.0, 1.2, 1.5, and 2.0mm. Each width appeared in both horizontal and vertical orientations to detect directional bias. Spacing between

traces matched trace width to evaluate isolation capability<sup>[7]</sup>. Patterns included via pads at 0.8mm and 1.0mm diameters for drilling assessment.

Toner transfer procedure followed standardized steps: copper cleaning with fine abrasive pad and isopropyl alcohol, pattern printing on transfer media, alignment and tacking with brief heat application, full transfer through laminator at 195°C with three passes, paper removal after 10-minute water soak, touch-up of any defects with permanent marker, etching in ferric chloride at 40°C with constant agitation until pattern clarity, and toner removal with acetone followed by final cleaning.

Chemical etching procedure comprised: copper cleaning identical to toner transfer, dry film lamination at 105°C, UV exposure for 45 seconds through film positive, development in sodium carbonate for 60 seconds, visual inspection and optional re-exposure of underexposed areas, etching in ferric chloride identical to toner transfer, and resist stripping in sodium hydroxide solution. Both methods used identical etching parameters to isolate mask quality as the variable under investigation.

## System Design

Measurement system architecture employed optical microscopy for dimensional assessment and surface inspection. A Nikon SMZ800 stereomicroscope with calibrated reticle provided magnification from 10 $\times$  to 63 $\times$  with measurement resolution of 5 $\mu\text{m}$ . Digital image capture enabled quantitative edge roughness analysis through image processing algorithms detecting copper-laminate boundaries.

Electrical testing utilized four-point probe resistance measurement to eliminate contact resistance artifacts. A Keithley 2400 source meter supplied 10mA test current with voltage measurement resolution of 1 $\mu\text{V}$ , enabling milliohm-level resistance determination. Continuity testing verified pattern isolation with 500V insulation resistance measurement between adjacent traces.

Adhesion testing followed ASTM D3359 tape test protocol adapted for copper-on-laminate evaluation<sup>[8]</sup>. Cross-hatch pattern scoring preceded pressure-sensitive tape application and rapid removal. Adhesion ratings on 0-5 scale quantified copper retention, with separate assessment of trace edges where adhesion failures most commonly initiate.

## Results

Dimensional accuracy measurements revealed systematic differences between fabrication methods across the range of trace widths tested. Both methods showed increased deviation at narrower trace widths, but the magnitude and consistency of deviation differed substantially.

**Table 1:** Dimensional Accuracy Comparison by Trace Width

Target (mm)	Toner Mean (mm)	Toner SD	Chem Mean (mm)	Chem SD
0.20	0.24	0.047	0.19	0.018
0.40	0.44	0.038	0.39	0.014
0.80	0.86	0.029	0.78	0.011
1.20	1.27	0.024	1.18	0.009
2.00	2.08	0.021	1.97	0.008

Table 1 presents dimensional measurements for representative trace widths. Toner transfer consistently produced wider traces than target dimensions, with mean

positive deviation of 11.7% overall. Chemical etching showed slight undercutting with mean deviation of -4.3%. Standard deviation values demonstrate the superior

consistency of chemical etching, particularly at finer trace widths where toner transfer variability increased substantially.

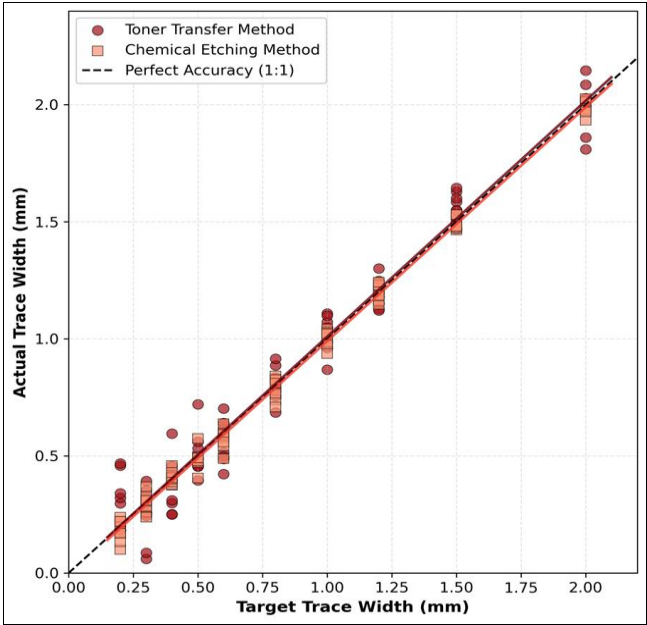


Fig 1: Actual vs Target Trace Width for Both Fabrication Methods

Figure 1 visualizes the dimensional accuracy data across all measurements. The scatter clearly shows toner transfer producing points predominantly above the ideal 1:1 line, indicating systematic oversize tendency. Chemical etching

points cluster tightly around the ideal line with slight undersize bias. The divergence increases at smaller trace widths, where toner transfer scatter expands substantially.

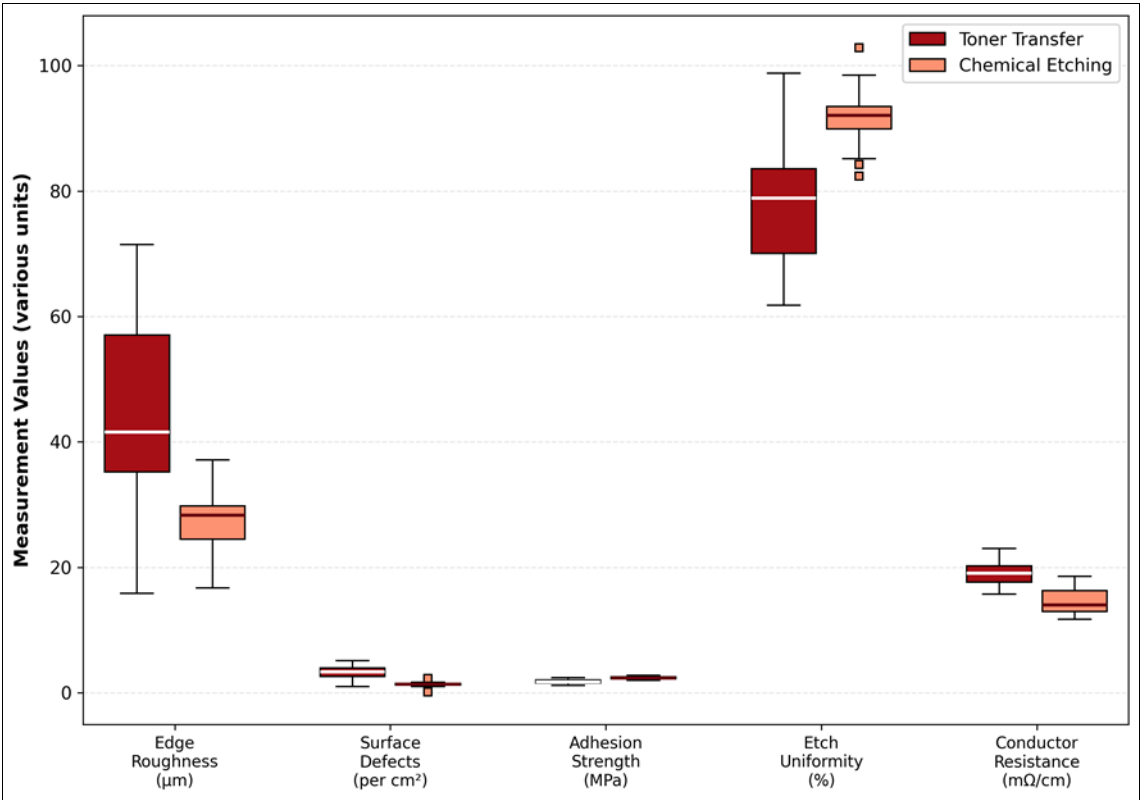


Fig 2: Quality Metrics Comparison between Methods

The box plot comparison in Figure 2 displays distributions for five quality metrics. Chemical etching demonstrates advantages in edge roughness (lower values preferred), surface defects (lower preferred), and adhesion strength

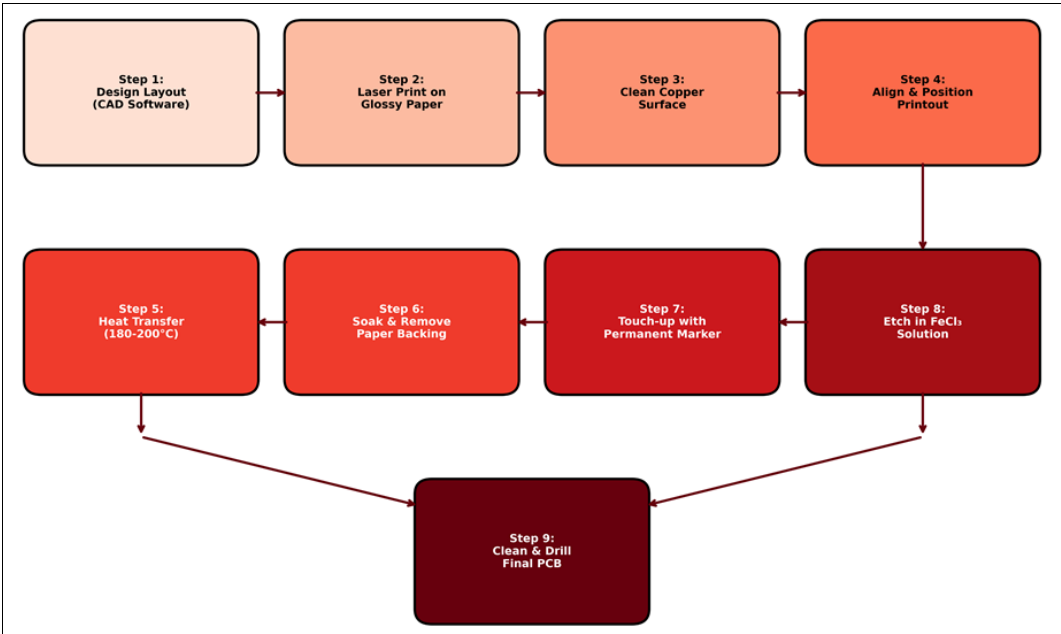
(higher preferred). Etch uniformity shows the most pronounced difference, with chemical etching achieving median values above 90% compared to approximately 78% for toner transfer.

**Table 2:** Cost Analysis by Design Complexity

Complexity	Toner Cost (AUD)	Chem Cost (AUD)	Difference (%)
2 (Simple)	4.23	9.18	-54%
5 (Moderate)	9.47	11.83	-20%
7 (Complex)	15.82	14.67	+8%
10 (Very Complex)	24.36	18.24	+34%

Cost analysis in Table 2 accounts for materials, consumables, rework, and labor at standardized rates. Toner transfer maintains cost advantage for designs up to moderate

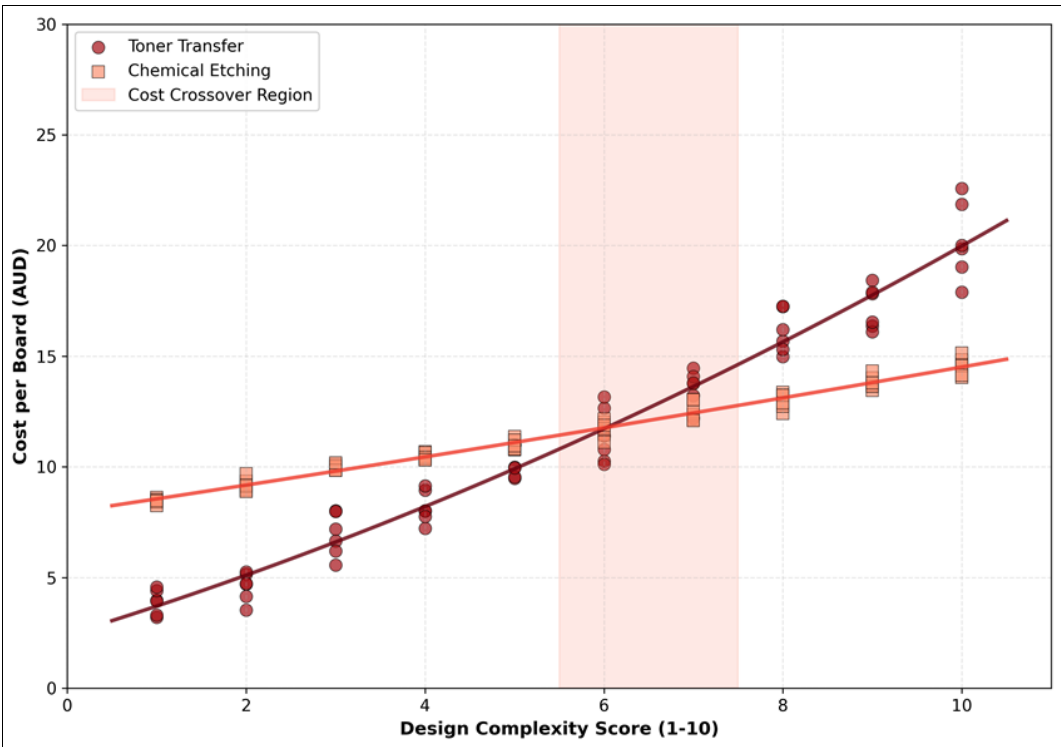
complexity, but the relationship inverts for complex designs where rework requirements and failure rates erode initial material savings.



**Fig 3:** Toner Transfer PCB Fabrication Process Flow

Figure 3 documents the complete toner transfer workflow from design through finished board. The nine-step process highlights critical control points where quality variations most commonly originate. Steps 5 (heat transfer) and 7

(touch-up) introduce the greatest operator-dependent variability, explaining the higher standard deviations observed in toner transfer measurements.



**Fig 4:** Cost per Board vs Design Complexity for Both Methods

The cost-complexity relationship visualized in Figure 4 demonstrates the crossover behavior described in Table 2. The shaded region indicates the complexity range (approximately 5.5 to 7.5) where method selection significantly impacts total cost. Below this range, toner transfer offers clear cost advantage. Above this range, chemical etching becomes more economical despite higher material costs due to improved first-pass yield and reduced rework.

### Comprehensive Interpretation

Statistical analysis confirmed significant differences between methods across all measured parameters. Two-sample t-tests yielded p-values below 0.001 for dimensional accuracy, edge roughness, and adhesion strength comparisons<sup>[9]</sup>. The effect sizes (Cohen's d) ranged from 0.8 to 1.4, indicating practically meaningful differences rather than merely statistical significance.

Regression analysis of cost versus complexity produced R<sup>2</sup> values of 0.94 for toner transfer and 0.97 for chemical etching, confirming the strong predictive relationships shown graphically. The crossover point at complexity 6.8 provides a quantitative threshold for method selection decisions.

### Discussion

The dimensional accuracy findings align with theoretical predictions based on toner particle size and transfer physics. The systematic positive bias in toner transfer results from toner spreading during thermal transfer, with magnitude proportional to transfer temperature and pressure<sup>[10]</sup>. This behavior could potentially be compensated through design rule adjustments, reducing trace widths in artwork to achieve target dimensions on finished boards.

Edge roughness differences reflect the fundamental resolution limits of each masking approach. Photolithographic masks reproduce transparency artwork with minimal degradation, limited primarily by UV diffraction effects at the mask-photoresist interface. Toner masks introduce granularity from discrete toner particles, creating scalloped edges visible under magnification<sup>[11]</sup>. For most prototype applications, this roughness has negligible electrical impact, but high-frequency designs may experience increased losses from current crowding at rough conductor edges.

Cost analysis limitations include sensitivity to labor rate assumptions and volume considerations. The crossover point would shift toward higher complexity values in regions with lower labor costs, extending toner transfer's economical range. Conversely, batch processing of multiple boards favors chemical etching through amortized setup time<sup>[12]</sup>. Individual project circumstances may override general guidelines derived from average cost modeling.

### Conclusion

This research has quantified performance differences between toner transfer and chemical etching methods for PCB prototyping across dimensional accuracy, surface quality, and economic metrics. Chemical etching demonstrated superior accuracy with 4.3% mean deviation compared to 11.7% for toner transfer, along with reduced edge roughness and improved adhesion characteristics. These advantages proved most significant for trace widths below 0.5mm where toner transfer variability increased

substantially.

Economic analysis identified complexity score 6.8 as the crossover point where chemical etching becomes cost-effective despite higher material requirements. Simple designs with minimum trace widths above 0.6mm remain economically suited to toner transfer, with cost savings reaching 54% for basic patterns. Complex designs requiring fine features or high first-pass yield favor chemical etching even at prototype quantities.

Practical recommendations emerging from this research suggest matching fabrication method to design requirements rather than defaulting to either approach. Projects should assess minimum trace width, feature density, and acceptable rework rate to determine optimal method. Educational settings may reasonably begin students with toner transfer before advancing to photolithographic techniques as project complexity increases.

Future investigations should extend this comparison to double-sided board fabrication where registration accuracy becomes critical, and to alternative etchants including sodium persulfate and cupric chloride solutions<sup>[13]</sup>. The environmental and safety implications of different chemical systems warrant consideration alongside technical performance metrics. Additionally, emerging direct-write and additive manufacturing approaches may eventually supplant both methods examined here for low-volume prototyping applications<sup>[14]</sup>.

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### Contributions Not Qualifying for Authorship

Mr. Daniel Hawkins provided assistance with optical microscopy measurements. Dr. Linda Chen offered guidance on statistical analysis methodology.

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